

**MD.26.**

<b>Title</b>	<b>The deposition process of ZnO films doped with Eu and functionalized with Pd</b>
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<b>Patent no.</b>	Patent application entry number 1974, 2019
<b>Description</b>	The invention relates to the technology for deposition of semiconductor oxide films, in particular to the process of obtaining of ZnO:Eu <sup>3+</sup> films, with application of rapid thermal annealing (T=650 °C, t=60s), with can be applied to the manufacture of gas sensors obtaining sensibility
<b>EN</b>	$S = I_{\text{gas}}/I_{\text{air}} = 1.3$ for 100 ppm H <sub>2</sub> gas at room temperature and $S = I_{\text{gas}}/I_{\text{air}} = 118$ at operating temperature of 250 °C.
<b>Class no.</b>	12. Safety, protection and rescue of people

INTERNATIONAL EXHIBITS